



12w

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Jung-ho LEE, et al.

Art Unit: 2818

Serial No. 10/779,733

Examiner: Renee R. Berry

Filed: February 18, 2004

Confirmation No. 2084

For: METHOD OF FORMING SILICON OXIDE LAYER
IN SEMICONDUCTOR MANUFACTURING
PROCESS

Attorney Docket No. 253/006 CIP 2

REPLY UNDER 37 C.F.R. §1.111

Mail Stop Amendments
Commissioner for Patents
P.O. Box 1450
Alexandria, Va. 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the Office action mailed June 13, 2005, please consider the following remarks:

A Listing of the Claims begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.